

Tero S Kulmala

List of Publications by Year in descending order

Source: <https://exaly.com/author-pdf/6119053/publications.pdf>

Version: 2024-02-01

13
papers

4,106
citations

1039406

9
h-index

1199166

12
g-index

13
all docs

13
docs citations

13
times ranked

8479
citing authors

| # | ARTICLE | IF | CITATIONS |
|----|---|-----|-----------|
| 1 | Quantifying Defects in Graphene via Raman Spectroscopy at Different Excitation Energies. Nano Letters, 2011, 11, 3190-3196. | 4.5 | 2,807 |
| 2 | Inkjet-Printed Graphene Electronics. ACS Nano, 2012, 6, 2992-3006. | 7.3 | 1,018 |
| 3 | Ultrafast and widely tuneable vertical-external-cavity surface-emitting laser, mode-locked by a graphene-integrated distributed Bragg reflector. Optics Express, 2013, 21, 31548. | 1.7 | 111 |
| 4 | Carbon nanotube thin film transistors based on aerosol methods. Nanotechnology, 2009, 20, 085201. | 1.3 | 45 |
| 5 | Platinum and palladium oxalates: positive-tone extreme ultraviolet resists. Journal of Micro/ Nanolithography, MEMS, and MOEMS, 2015, 14, 043511. | 1.0 | 35 |
| 6 | SnOx high-efficiency EUV interference lithography gratings towards the ultimate resolution in photolithography. Microelectronic Engineering, 2016, 155, 44-49. | 1.1 | 34 |
| 7 | Novel carbon nanotube network deposition technique for electronic device fabrication. Physica Status Solidi (B): Basic Research, 2008, 245, 2272-2275. | 0.7 | 14 |
| 8 | Self-Aligned Coupled Nanowire Transistor. ACS Nano, 2011, 5, 6910-6915. | 7.3 | 12 |
| 9 | EUV lithography process challenges. Frontiers of Nanoscience, 2016, 11, 135-176. | 0.3 | 9 |
| 10 | Toward 10Ånm half-pitch in extreme ultraviolet lithography: results on resist screening and pattern collapse mitigation techniques. Journal of Micro/ Nanolithography, MEMS, and MOEMS, 2015, 14, 033507. | 1.0 | 8 |
| 11 | Toward 10nm half-pitch in EUV lithography: results on resist screening and pattern collapse mitigation techniques. Proceedings of SPIE, 2015, , . | 0.8 | 7 |
| 12 | Pattern collapse mitigation in inorganic resists via a polymer freeze technique. Microelectronic Engineering, 2016, 155, 39-43. | 1.1 | 6 |
| 13 | A bottom-up pattern collapse mitigation strategy for EUV lithography. Proceedings of SPIE, 2016, , . | 0.8 | 0 |